

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Claims.

Sub 17  
1. (Amended) A method, comprising:

cleaning a plasma reactor chamber part of a material redistributed thereon by a reactive plasma process, by placing the chamber part in a redistributed material solvent.

10 10. (Amended) A method of cleaning a plasma reactor chamber part, comprising:

plasma cleaning a chamber part of a material redistributed on the chamber part by a reactive plasma process, with a plasma having an etch selectivity between the chamber part and the redistributed material that is greater than 1:100.

15